

A B S T R A C T

A film formation method includes a preparation stage (S10) and a process stage (S20). In the preparation stage (S10), a process time correction equation prepared to correct process time in accordance with atmospheric pressure is derived, based on a first relational equation that expresses a relationship between film thickness and process time, and a second relational equation that expresses a relationship between atmospheric pressure and film thickness (S11 to S14). In the process stage (S20), process time is corrected, based on the process time correction equation thus derived and a measurement result of current atmospheric pressure, and then film formation is performed, based on process time thus corrected (S21 to S23).